
PATENT ABSTRACTS OF JAPAN

(11)Publication number : 2000-019732
 (43)Date of publication of 21.01.2000
 application :

(51)Int.Cl. G03F 7/039
 C08F 2/48
 C08L 25/02
 C08L 33/04
 C08L 45/00
 H01L 21/027

(21)Application number :	10-182641	(71)Applicant : TOSHIBA CORP
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(54) POLYMER FOR PHOTOSENSITIVE COMPOSITION AND PATTERN FORMING METHOD USING IT

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a photosensitive composition, excellent in light transmissivity, excellent in dry-etching tolerance, high in reaction efficiency by an acid catalyst, and excellent in adhesiveness to a substrate, and a pattern forming method giving an excellent pattern shape.

SOLUTION: This photosensitive composition includes an optical acid- producing agent and a copolymer having molecular-weight distribution given by the ratio Mw/Mn of weight-average molecular weight Mw to number-average molecular weight Mn of 1.0 to 1.4 and obtained by living-polymerizing a vinyl monomer having an alicyclic skeleton or a naphthalene skeleton, and/or a (meta) acrylic ester monomer, and this pattern forming method is for developing a photosensitive material using the same by exposing it to light of short wavelengths.

LEGAL STATUS

[Date of request for examination]	14.03.2001
[Date of sending the examiner's decision of rejection]	25.07.2003
[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]	
[Date of final disposal for application]	
[Patent number]	
[Date of registration]	
[Number of appeal against examiner's decision of rejection]	

[Date of requesting appeal against examiner's decision of
rejection]

[Date of extinction of right]